

**Notice of References Cited**

Application/Contr

09/678,793

Applicant(s)/Patent Under  
Reexamination  
KANNO ET AL.

Examiner

Lynette T. Umez-Eronini

Art Unit

1765

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**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5715173	02-1998	Nakajima et al.	364/500
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Kenta et al., Developer For Photoresist, Computer generated English translation of JP 10319606 A, December 4, 1998, 5 pages.
	V	Yasuo et al., Cleaning Solution for Silicon Wafer and Semiconductor Device, Computer generated English translation of JP 06013364 A, January 21, 1994, 6 pages.
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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